

Studies on the Preparation and Properties of Conductive Polymers. Part II. Novel Method to Prepare Metallized Plastics from Metal Chelates of Polyamides

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SYNOPSIS

New metallized films were obtained by the reduction of polyamide metal chelate films with reducing agents. Polyamide metal chelates films exhibited excellent surface resistivity around 10^0 – $10^1 \Omega/\text{cm}^2$ when treated with sodium borohydride aqueous solutions. Aqueous solutions of polyamide–formic acid with metal salts, and films prepared from those solutions, were analyzed by UV-visible and IR spectroscopy, respectively, in order to investigate and identify the structure of the polyamide metal chelates. Factors that include kinds and concentrations of metal salts, kinds and concentrations of reducing agents, and reduction time, which may affect the conductivity of metallized films, were investigated. The surfaces of these films were treated with sodium borohydride aqueous solution to form a definite metallic luster appearance. The surfaces of these conductive films were proved to be metallized, by means of ESCA analysis. The strongly adhered metal on the films was believed to be responsible for the improvement in electrical conductivity. The mechanical properties and scanning electron microscope (SEM) observations were also studied.

INTRODUCTION

Electrically conducting polymers have recently been the subject of intense interest. The doping of neutral polymers with dissolved metal salts or metal complexes for the purpose of imparting electrical conductivity to the polymer has received much attention. The surface electrical conductivity of films of poly(vinyl alcohol)– Cu^{2+} and polyacrylamide– Cu^{2+} have been shown^{1,2} to increase by spreading an acetone solution of iodine over the film surfaces. After iodine treatment, a whitish substance identified as γ -CuI is believed to be responsible for the enhanced electrical conductivity. However, these conductive films were very unstable in air, and their surface resistivity only reached about 10^3 – $10^4 \Omega/\text{cm}^2$, therefore, they are of less practical use.

In order to develop easily processed metallized films, there have been attempts to use polymers as a base for the films and further chemically modify

them so as to obtain good electrical conductivity. A new metallized film with good conductivity obtained from poly(vinyl alcohol) metal chelate film treated with reducing agents was prepared successfully as described in the first paper of this series.³

In this investigation, nylon 4 and nylon 6 with amide groups capable of forming metal chelates are used as another class of easily processable polymer. It was found that polyamide metal chelate film reduced by sodium borohydride solution also showed similar conductivity to that of the poly(vinyl alcohol) metal chelate film.

EXPERIMENTAL

Nylon 4 Synthesis

Nylon 4 was synthesized by the CO_2 -initiated polymerization of 2-pyrrolidone using potassium 2-pyrrolidonate as the catalyst.^{4,5} The molecular weight of the samples, measured in *m*-cresol at 25°C by a Cannon-Fenske viscometer was about 20,000

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to 42,000. In this study, nylon 4 with a molecular weight of about 25,000 was used.

Purification of Nylon 6

Commercially available nylon 6 with a molecular weight of 16,000 was used. Nylon 6 was dissolved in formic acid, and the resulting solution was poured into distilled water. Precipitation of the nylon 6 took place immediately. The precipitate was washed thoroughly with water and dried in a vacuum oven to obtain the refined nylon 6.

Preparation of Polyamide Metal Chelate Film

Polyamide metal chelate films were prepared by the following two methods:

Mixed Method

The nylon-formic acid solution comprised 10–12 wt % nylon in an 88–90 wt % mixture of 4 : 1 (v/v) 90% formic acid solution and *n*-PrOH. The ratio of the molar concentration of metal ion to that of monomeric units of the nylon ($F = [M^{n+}]/[MU]$) was adjusted by adding the proper amounts of the metal salt aqueous solution to the nylon-formic acid solution. Various conditions used are shown in Table II and Table III.

Solution of the mixtures were stirred at room temperature for 24 h. The resulting viscous solutions were cast on clean glass plates. The films on the glass plates were evaporated at ambient for 5 min and further dried in an oven at 80°C for 30 min. The films were then peeled off and cut into 1 × 3 cm pieces for subsequent uses.

Soak Method

The polyamide solution comprised of 10–12 wt % nylon and 88–90 wt % mixture of 4 : 1 (v/v) 90% formic acid solution and *n*-PrOH was cast on a clean glass plate. The film on the glass plate was evaporated for 5 min at ambient, heated in an oven at 80°C for 30 min, and then cooled to room temperature for 10 min. The film cast on the glass plate was immersed in a methanol bath at room temperature for 10 min. The film was then peeled off and stored in water for at least 12 h before subsequent use. The film was cut into a 1 × 3 cm test piece. The test piece was soaked in 100 mL of a suitable concentration of aqueous metal salt solution containing 0.04 g of nonionic surfactant (polyethylene glycol mono-*p*-nonylphenyl ether, *n* = 15) in an oven at

50°C for a suitable time, was dried for a few minutes in air, and further dried in an oven at 80°C for 30 min.

Preparation of Metallized Polyamide Films by Metalhydride Reducing Agents

The test pieces of polyamide metal chelate films were reduced by 25 mL of a 0.2–4.0 wt % sodium borohydride aqueous solution containing 0.04 g of non-ionic surfactant (polyethylene glycol mono-*p*-nonylphenyl ether, *n* = 15) at 40–80°C for a suitable time. The reduced films were washed with water and dried at 100°C for 5 min, then cooled to room temperature and stored in a desiccator for subsequent use. Other reducing agents including lithium aluminum hydride (LiAlH₄), lithium hydride (LiH), sodium hydride (NaH), calcium hydride (CaH₂), and sodium (Na) were also tested and were unsuccessful (Table IV).

Electric Measurement

The surface electrical conductivity of the films was measured according to the conventional four-terminal method using aluminum foil electrodes, as described previously.²

Instrument Analysis

Visible and UV absorption spectral data of the polyamide metal chelate films were obtained by using a Shimadzu model UV-160 spectrophotometer. IR spectra of polyamide metal chelate films ranging from 4000 to 400 cm⁻¹ were obtained by using the Perkin-Elmer 710B spectrophotometer. Electron spectroscopy for chemical analysis (ESCA) spectra were obtained by using a VG Scientific LTD model LAB 5 spectrometer with a Mg K_α X-ray source with radiation generated at 10 kV and 20 mA. The surfaces of unreduced and reduced samples coated with gold film of 150 Å thickness, were measured by a Hitachi Model S570 scanning electron microscope (SEM).

Measurement of Mechanical Strength

The tensile strengths and elongations of unreduced and reduced samples were measured by the Toyo Baldwin type TENSILON/UTM-III-100 instrument at ambient. The tensile strengths and elongations of samples in their dry states were measured according to ASTM D638 method.⁶

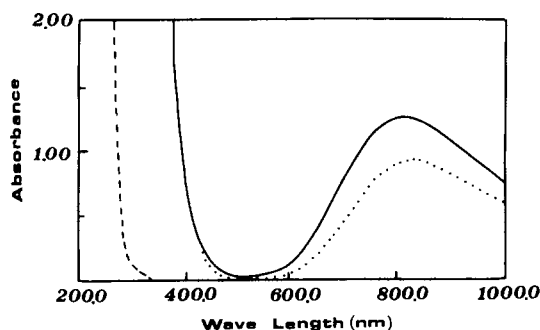


Figure 1 Visible and UV absorption spectra. (a) (---) nylon 4-HCOOH solution; (b) (···) CuCl_2 -HCOOH solution; (c) (—) nylon 4- CuCl_2 -HCOOH solution.

RESULTS AND DISCUSSION

Visible and UV Spectra Observations

The formation of PVA- Ag^+ chelate identified from UV-visible spectra was reported in our previous paper.³ In this study the formation of polyamide metal chelate can also be identified from UV-visible spectra. Nylon 4 or nylon 6 shows no absorbance in the visible region, as shown in Figure 1(a). The UV-

visible spectral band of the CuCl_2 -HCOOH solution appears at 825 nm, as shown in Figure 1(b). When the CuCl_2 -HCOOH solution is added to the nylon 4 (or nylon 6)-formic acid solution and constantly stirred for 24 h, the UV-visible spectral band is shifted to a shorter wavelength, which absorbs at about 800–802 nm, as shown in Figure 1(c). Similarly, the UV-visible spectral band of nylon 4 (or nylon 6)- NiCl_2 and nylon 4 (or nylon 6)- CoCl_2 solution are also shifted to shorter wavelengths, compared to those of the NiCl_2 -HCOOH and CoCl_2 -HCOOH solution, as shown in Table I. From these results the formation of polyamide metal chelate, from metal ion coordinated with the amide group of polyamide, was indicated.

IR Analysis

As mentioned, polyamide metal chelate was formed for metal ion coordinated with polyamide. In order to confirm the chelate formation and further investigate the structure of the metal chelate, IR spectra were measured for polyamide metal chelate films prepared from the mixtures of polyamide solutions and various concentrations of CuCl_2 as well as NiCl_2 .

Table I Absorption Wavelength of Formic Acid Solution of Metal Salts and Formic Acid Solution of Nylon/Metal Salts

Polymer	Metal Salts	F^a	Wt % ^b	Absorption Wavelength (nm)
—	$\text{CuCl}_2 \cdot 2\text{H}_2\text{O}$	—	0.30	825
—	$\text{CuCl}_2 \cdot 2\text{H}_2\text{O}$	—	0.50	825
—	$\text{NiCl}_2 \cdot 6\text{H}_2\text{O}$	—	0.28	742, 403, 312
—	$\text{NiCl}_2 \cdot 6\text{H}_2\text{O}$	—	0.70	742, 403, 312
—	$\text{CoCl}_2 \cdot 6\text{H}_2\text{O}$	—	0.43	518, 362
—	$\text{CoCl}_2 \cdot 6\text{H}_2\text{O}$	—	0.70	518, 362
Nylon 4	$\text{CuCl}_2 \cdot 2\text{H}_2\text{O}$	0.03	0.30	800
Nylon 4	$\text{CuCl}_2 \cdot 2\text{H}_2\text{O}$	0.05	0.50	800
Nylon 4	$\text{NiCl}_2 \cdot 6\text{H}_2\text{O}$	0.02	0.28	733, 394
Nylon 4	$\text{NiCl}_2 \cdot 6\text{H}_2\text{O}$	0.05	0.70	733, 394
Nylon 4	$\text{CoCl}_2 \cdot 6\text{H}_2\text{O}$	0.03	0.43	523
Nylon 4	$\text{CoCl}_2 \cdot 6\text{H}_2\text{O}$	0.05	0.53	523
Nylon 6	$\text{CuCl}_2 \cdot 2\text{H}_2\text{O}$	0.03	0.23	802
Nylon 6	$\text{CuCl}_2 \cdot 2\text{H}_2\text{O}$	0.05	0.38	802
Nylon 6	$\text{NiCl}_2 \cdot 6\text{H}_2\text{O}$	0.02	0.21	735, 394
Nylon 6	$\text{NiCl}_2 \cdot 6\text{H}_2\text{O}$	0.05	0.53	735, 394
Nylon 6	$\text{CoCl}_2 \cdot 6\text{H}_2\text{O}$	0.03	0.32	523
Nylon 6	$\text{CoCl}_2 \cdot 6\text{H}_2\text{O}$	0.05	0.53	523

^a Molar concentration of metal ions to that of monomeric units of the nylon.

^b Based on formic acid weight.

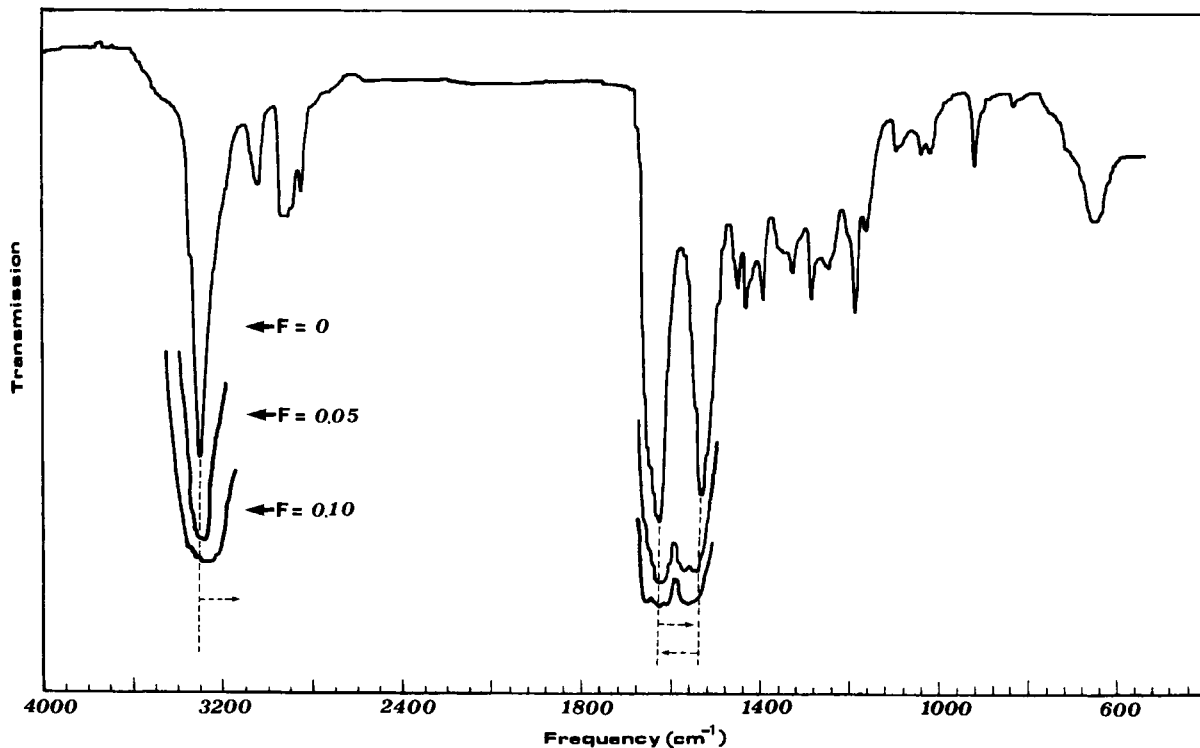


Figure 2 Infrared absorption spectra of nylon 4-CuCl₂ films with different *F* value.

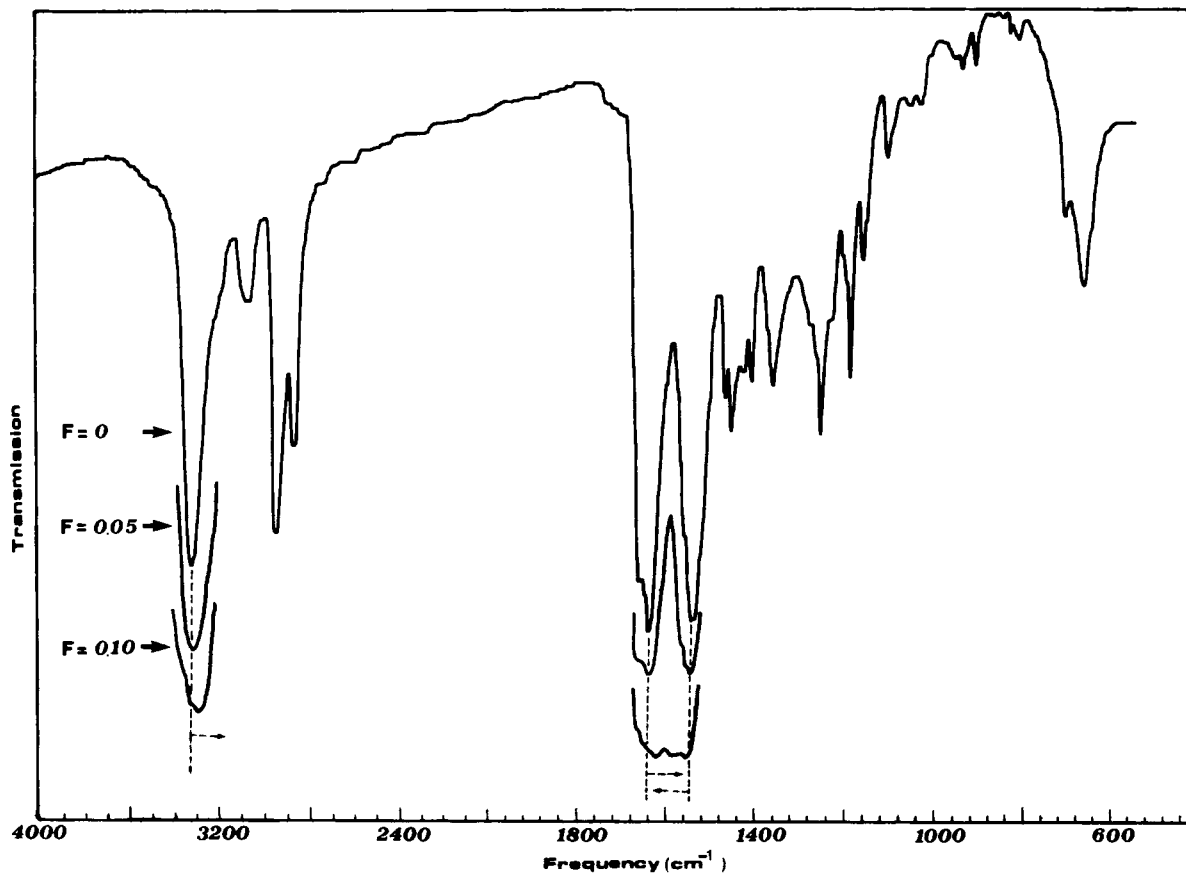


Figure 3 Infrared absorption spectra of nylon 6-CuCl₂ films with different *F* value.

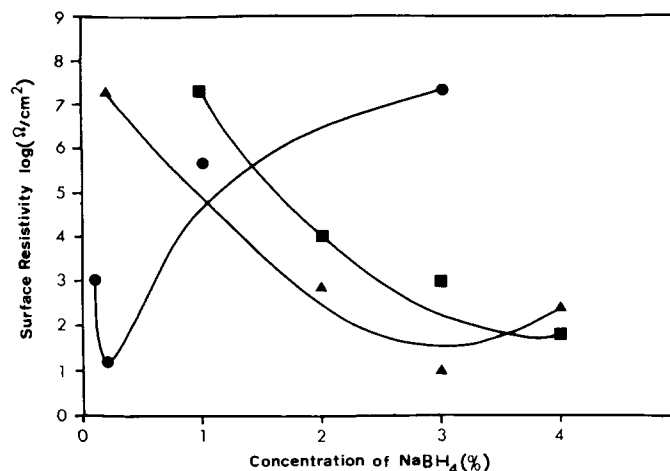


Figure 4 Variation of surface resistivity of nylon 4 metal chelate films with the concentration of NaBH₄ aqueous solution. (■) nylon 4-CoCl₂·6H₂O; (▲) nylon 4-CuCl₂·2H₂O; (●) nylon 4-NiCl₂·6H₂O.

The IR spectra for nylon 4 and nylon 6 with CuCl₂ of $F = 0, 0.05, \text{ and } 0.1$ are shown in Figures 2 and 3, respectively. It should be noticed that a peak due to the C=O stretching band at 1640 cm^{-1} shifts to shorter frequency with increasing F value, and another peak due to the C-NH stretching band at 1540 cm^{-1} shifts to longer frequency with increasing F value. Another spectral change is also observed in the peak due to the N-H stretching band at 3290 cm^{-1} , which shifts to a lower frequency with increasing F value. Moreover, these absorption bands get broader with increasing F value. The IR spectra

for nylon 4-NiCl₂ and nylon 6-NiCl₂ chelate films are similar to those of nylon 4-CuCl₂ and nylon 6-CuCl₂ chelate films. From these results chelate formation is confirmed for Cu²⁺ or Ni²⁺ coordinated with amide group of nylon 4 and nylon 6.

Effects of the Concentration of Reducing Agents on the Conductivity of Nylon 4 Metal Chelate Films

In this study sodium borohydride (NaBH₄) is shown to be a suitable reducing agent to reduce polyamide

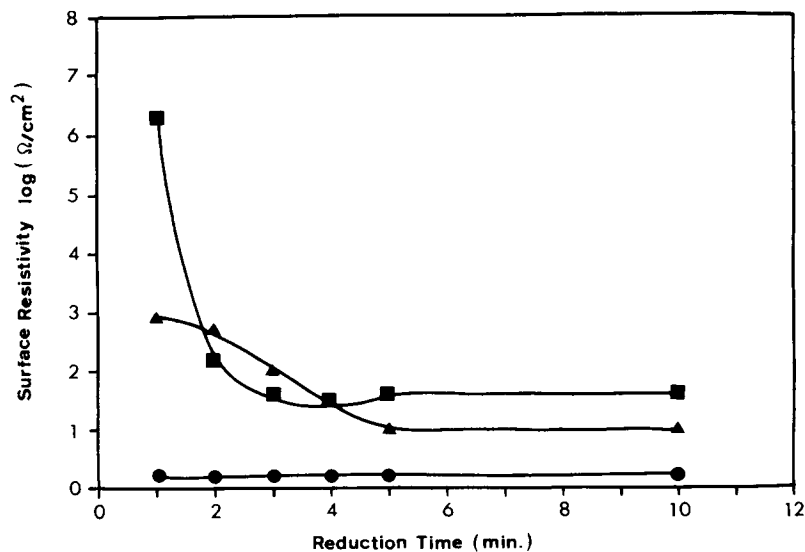


Figure 5 Effect of reduction time of NaBH₄ aqueous solution on the surface resistivity of nylon 4-CuCl₂ chelate film (reduction temperature = 75°C). (■) $F = 0.06$; (▲) $F = 0.10$; (●) $F = 0.20$.

metal chelate films. The effects of various concentrations of NaBH_4 on the conductivity of nylon 4 metal chelate films are shown in Figure 4. These metal chelate films were prepared by the mixed method as mentioned in the experimental section. Nylon 4- Cu^{2+} chelate film was treated with 0.2 wt % NaBH_4 aqueous solution and showed a surface resistivity over $2 \times 10^7 \Omega/\text{cm}^2$. The surface resistivity of this film is decreased with increasing concentration of NaBH_4 aqueous solution up to a concentration of 3.0 wt %. When nylon 4- CuCl_2 chelate film was reduced by 3.0 wt % NaBH_4 aqueous solution, it showed a low surface resistivity of about $1.0 \times 10^1 \Omega/\text{cm}^2$. Therefore, a suitable concentration of NaBH_4 to reduce nylon- Cu^{2+} chelate film is 3.0 wt %. Similarly, suitable concentrations of NaBH_4 to reduce nylon- Ni^{2+} and nylon- Co^{2+} are 0.2 and 4.0 wt %, respectively.

Effects of Reduction Time on the Conductivity of Polyamide-Metallized Films

The nylon 4 metal chelate films are treated with NaBH_4 aqueous solution at different reduction times ranging from 10 s to 10 min. As shown in Figure 5, when $F = 0.06$ for nylon 4- Cu^{2+} chelate film treated with NaBH_4 aqueous solution for 4 min, the film shows excellent conductivity. When $F = 0.1$ and $F = 0.2$ for nylon 4- Cu^{2+} chelate films, suitable reduction times for preparing excellent conductivity films are 5 and 1 min, respectively. Similarly, the most appropriate reduction time for preparing the

nylon 4- Ni^{2+} chelate films ($F = 0.05$ and $F = 1.0$) having excellent conductivity are 3 to 5 min, which is shown in Figure 6.

Effects of the Amount of Metal Salts in Polyamide Metal Chelate Films on the Conductivity of Metallized Films

As shown in Table II, when $F = 0.05$ of nylon 4- Cu^{2+} chelate film is treated with NaBH_4 aqueous solution, surface resistivity shows still over $2 \times 10^7 \Omega/\text{cm}^2$. When $F > 0.05$, the surface resistivity of films treated with NaBH_4 aqueous solution decreases with increasing F values. When $F > 0.1$, the films exhibited low surface resistivity, about $10^0 \Omega/\text{cm}^2$ after the NaBH_4 aqueous solution treatment. The nylon 4- Ni^{2+} and nylon 4- Co^{2+} chelate films shows excellent conductivity after the NaBH_4 aqueous solution treatment, with $F > 0.03$ and $F > 0.06$, respectively. Similarly, the surface resistivity of nylon 6 metal chelate films after NaBH_4 aqueous solution treatment show a decrease with an increase of F values, as shown in Table III. In general, the films with $F > 0.2$ did not improve the electrical conductivity and had unsatisfactory effects on the mechanical properties.

Effects of the Solvents on the Reduction of Polyamide Metal Chelate Films

In this study polyamide metal chelate films were reduced by certain agents in various solvents. As

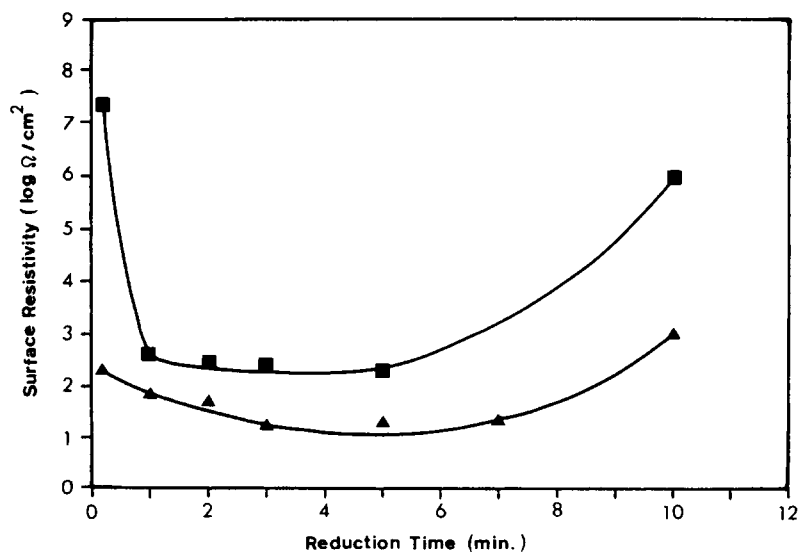


Figure 6 Effect of reduction time of NaBH_4 aqueous solution on the surface resistivity of nylon 4- NiCl_2 chelate film (reduction temperature = 40°C). (■) $F = 0.05$; (▲) $F = 0.10$.

Table II Effect of the Concentration of Metal Salts on the Surface Resistivity of Nylon 4 Metal Chelate Films Reduced by NaBH₄ Aqueous Solution

Metal Salts	F ^a	Wt % ^b	Surface Resistivity (Ω/cm ²)
CuCl ₂ · 2H ₂ O ^c	0.05	10.0	> 2 × 10 ⁷
	0.06	12.0	3.0 × 10 ⁴
	0.08	16.0	2.6 × 10 ⁴
	0.09	18.0	2.0 × 10 ⁴
	0.10	20.0	1.0 × 10 ⁴
	0.125	25.0	4.0 × 10 ⁰
	0.150	30.0	3.0 × 10 ⁰
	0.175	35.0	3.0 × 10 ⁰
NiCl ₂ · 6H ₂ O ^d	0.02	5.6	> 2 × 10 ⁷
	0.03	8.4	1.0 × 10 ⁵
	0.04	11.2	3.2 × 10 ²
	0.05	14.0	2.4 × 10 ²
	0.07	19.6	8.0 × 10 ¹
	0.10	28.0	1.7 × 10 ¹
	0.125	35.0	1.8 × 10 ²
	0.150	42.0	1.8 × 10 ²
CoCl ₂ · 6H ₂ O ^e	0.04	11.2	> 2 × 10 ⁷
	0.06	16.8	3.0 × 10 ⁴
	0.08	22.4	2.5 × 10 ²
	0.10	28.0	1.8 × 10 ¹
	0.175	49.0	9.0 × 10 ⁰

^a Molar concentration of metal ions to that of monomeric units of the nylon 4.

^b Based on the nylon 4 weight.

^c Concentration of NaBH₄ solution = 3.0 wt %, temperature = 75°C.

^d Concentration of NaBH₄ solution = 0.2 wt %, temperature = 40°C.

^e Concentration of NaBH₄ solution = 4.0 wt %, temperature = 80°C.

shown in Table IV, polyamide metal chelate films showed excellent electrical conductivity when they were reduced by NaBH₄ aqueous solution. Other agents, such as lithium aluminum hydride (LiAlH₄) in tetrahydrofuran (or diethyl ether), sodium (Na), lithium hydride (LiH), sodium hydride (NaH), and calcium hydride (CaH₂) in ethanol were used, but these films show high surface resistivity (> 2 × 10⁷ Ω/cm²). When these metal chelate films were dipped into water, the metal ions in the metal chelate films diffused out and were detected by a UV-visible spectrophotometer. When these metal chelate films were also dipped into other solvents such as tetrahydrofuran, diethyl ether, and ethanol, metal ions

did not diffuse out and showed no absorbance by UV-visible spectroscopy. These results can be explained by metal ions of the polyamide metal chelate films not being able to diffuse out of the nonaqueous solvents used for reducing agents other than the water solution of NaBH₄. Therefore, no reduction is happening even though these reducing agents are more reactive than NaBH₄.

Effects of the Concentrations of Metal Salt Solutions on the Electrical Conductivity of Metallized Films Prepared by the Soak Method

The polyamide metal chelate films used were prepared by the soak method. As shown in Table V, when the concentration of metal salt is less than 30 wt %, such as 10 and 20 wt %, the nylon films shows unsatisfactory conductivity after treatment with NaBH₄ aqueous solution. Nylon 4 or nylon 6 films were soaked in 30 wt % metal salts solution for 60 h to produce the metal chelate films. These films exhibited surface resistivity around 10¹–10² Ω/cm²

Table III Effect of the Concentration of Metal Salts on the Surface Resistivity of Nylon 6 Metal Chelate Films Reduced by NaBH₄ Aqueous Solution

Metal Salts	F ^a	Wt % ^b	Surface Resistivity (Ω/cm ²)
CuCl ₂ · 2H ₂ O ^c	0.06	9.0	> 2 × 10 ⁷
	0.08	12.0	5.0 × 10 ⁴
	0.10	15.0	4.8 × 10 ⁴
	0.15	22.6	2.5 × 10 ⁴
	0.20	30.1	4.0 × 10 ⁰
NiCl ₂ · 6H ₂ O ^d	0.02	4.2	> 2 × 10 ⁷
	0.03	6.3	2.0 × 10 ⁶
	0.05	10.5	3.4 × 10 ³
	0.10	21.0	1.5 × 10 ²
	0.15	31.6	6.0 × 10 ¹
CoCl ₂ · 6H ₂ O ^e	0.04	8.4	> 2 × 10 ⁷
	0.06	12.6	> 2 × 10 ⁷
	0.08	16.8	4.0 × 10 ³
	0.10	21.0	8.0 × 10 ²
	0.15	31.6	6.5 × 10 ¹

^a Molar concentration of metal ions to that of monomeric units of the nylon 6.

^b Based on the nylon 6 weight.

^c Concentration of NaBH₄ solution = 3.0 wt %, temperature = 75°C.

^d Concentration of NaBH₄ solution = 0.2 wt %, temperature = 40°C.

^e Concentration of NaBH₄ solution = 4.0 wt %, temperature = 80°C.

Table IV Effect of Reducing Agents in Various Solvents on the Surface Resistivity of Polyamide Metal Chelate Film

Reducing Agents	Solvents	Concentration (Wt %)	Reduction Temp. (°C)	Surface Resistivity (Ω/cm^2)
NaBH ₄	Water	0.2-4.0	40-80	10 ⁰ -10 ¹
LiAlH ₄	Tetrahydrofuran	1.0-3.0	0-10	> 2 × 10 ⁷
LiAlH ₄	Diethyl ether	1.0-3.0	0-10	> 2 × 10 ⁷
Na	Ethanol	8.0-10.0	78	> 2 × 10 ⁷
LiH	Ethanol	1.0-3.0	20-50	> 2 × 10 ⁷
NaH	Ethanol	1.0-3.0	20-50	> 2 × 10 ⁷
CaH ₂	Ethanol	1.0-3.0	20-50	> 2 × 10 ⁷

after treating with NaBH₄ aqueous solution. When the concentration of metal salt is higher than 30 wt %, nylon films show some cracks after being soaked for 60 h. Therefore, the suitable concentration of metal salts for preparing metallized film is 30 wt %.

ESCA Analysis

Electron spectroscopy chemical analysis (ESCA) was used to analyze the surface of the metallized

films. The ESCA spectrum of nylon 4 metallized film after argon sputtering for 5 min is shown in Figures 7 and 8. In Figure 7 the electron binding energies of Cu 2p_{3/2} is 933.15 eV and Cu 2p_{1/2} is 952.95 eV. In Figure 8 the electron binding energies of Ni 2p_{3/2} is 853.25 eV and Ni 2p_{1/2} is 870.65 eV. These results are consistent with the ESCA handbook.⁷ From these results Cu²⁺ and Ni²⁺ have been reduced to metallic Cu and metallic Ni on these films as indicated.

Table V Variation of Surface Resistivity of Metallized Nylon Films Prepared from Nylon Films Soaked in Various Concentrations of Metal Salts Aqueous Solution for 60 h

Species	Metal Salts	Concentration (%)	Surface Resistivity (Ω/cm^2)
Nylon 4	CuCl ₂ · 2H ₂ O ^a	10.0	1.0 × 10 ⁶
		20.0	7.0 × 10 ¹
		30.0	4.0 × 10 ¹
	NiCl ₂ · 6H ₂ O ^b	10.0	4.0 × 10 ³
		20.0	1.7 × 10 ²
		30.0	7.0 × 10 ¹
	CoCl ₂ · 6H ₂ O ^c	10.0	> 2 × 10 ⁷
		20.0	1.0 × 10 ³
		30.0	2.5 × 10 ¹
Nylon 6	CuCl ₂ · 2H ₂ O ^d	10.0	1.0 × 10 ²
		20.0	7.0 × 10 ¹
		30.0	2.0 × 10 ¹
	NiCl ₂ · 6H ₂ O ^e	10.0	1.3 × 10 ²
		20.0	1.0 × 10 ²
		30.0	3.5 × 10 ¹
	CoCl ₂ · 6H ₂ O ^f	10.0	> 2 × 10 ⁷
		20.0	1.0 × 10 ⁵
		30.0	5.1 × 10 ²

^a Concentration of NaBH₄ solution = 2.0 wt %, temp. = 70°C, time = 30 s.

^b Concentration of NaBH₄ solution = 0.8 wt %, temp. = 45°C, time = 30 s.

^c Concentration of NaBH₄ solution = 4.0 wt %, temp. = 65°C, time = 30 s.

^d Concentration of NaBH₄ solution = 2.0 wt %, temp. = 70°C, time = 10 s.

^e Concentration of NaBH₄ solution = 0.8 wt %, temp. = 45°C, time = 10 s.

^f Concentration of NaBH₄ solution = 4.0 wt %, temp. = 65°C, time = 10 s.

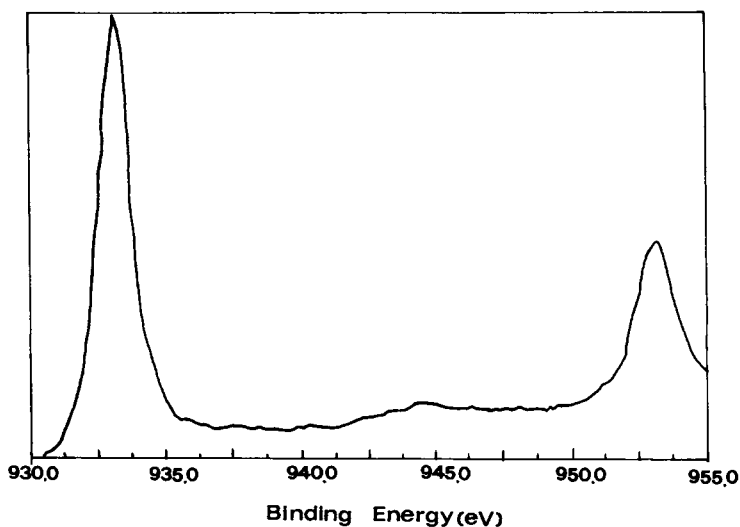
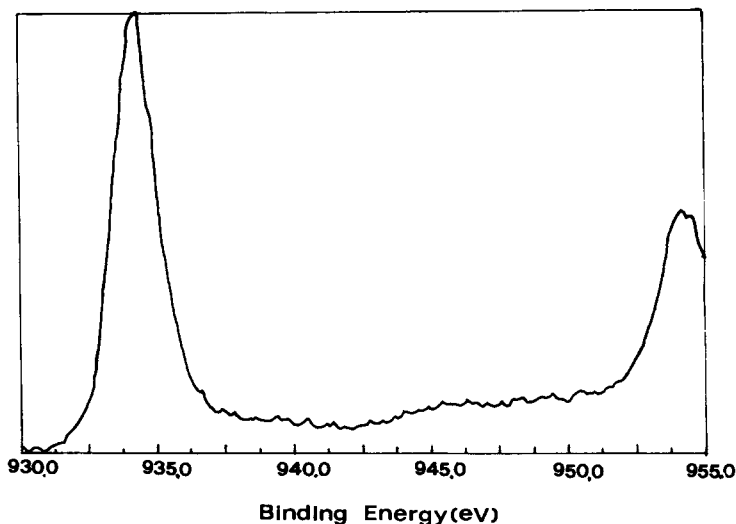


Figure 7(a) ESCA spectrum of unreduced nylon 4-Cu²⁺ chelate film.

Figure 7(b) ESCA spectrum of nylon 4-Cu²⁺ chelate film reduced by NaBH₄ aqueous solution.

A 50/50 by weight mixture of cupric chloride and nickel chloride solutions was added to the polyamide-formic acid solution. The mixture was stirred at room temperature for 24 h and dried to a film as reported in the experimental section. The film was then reduced by NaBH₄ aqueous solution to provide excellent conductivity. The results of ESCA indicate only Ni²⁺ has been reduced to Ni on the film surface. It indicates that Cu²⁺ first formed a metal chelate with the amide group of polyamide and Ni²⁺ was then connected with Cu²⁺ by Cl⁻ in the outer position. Therefore, only Ni²⁺ was reduced by NaBH₄

solution to Ni on the film surface. A precise study is now in progress and will be reported in the near future.

Scanning Electron Microscope Observations

An SEM photograph shows a very flat surface on the nylon 4-CuCl₂ chelate film [Fig. 9(a)]. A drastic change of surface features occurs upon treatment with reducing agents, as shown in Figure 9(b). An extremely rough surface for the nylon 4-CuCl₂ chelate film results after NaBH₄ treatment. In Figure

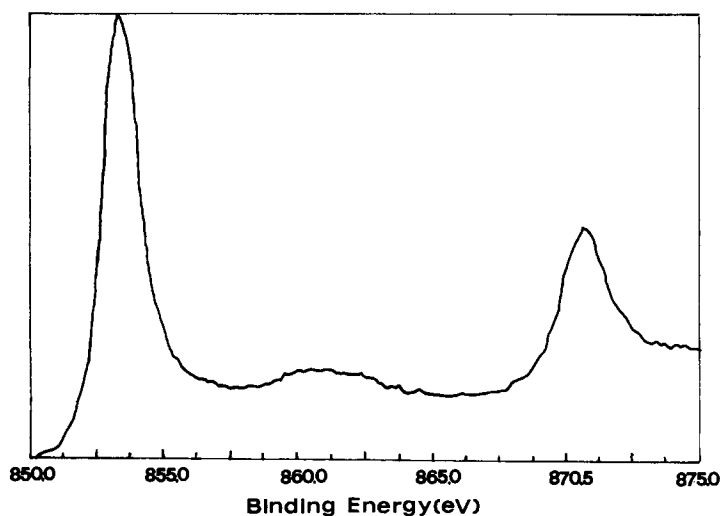
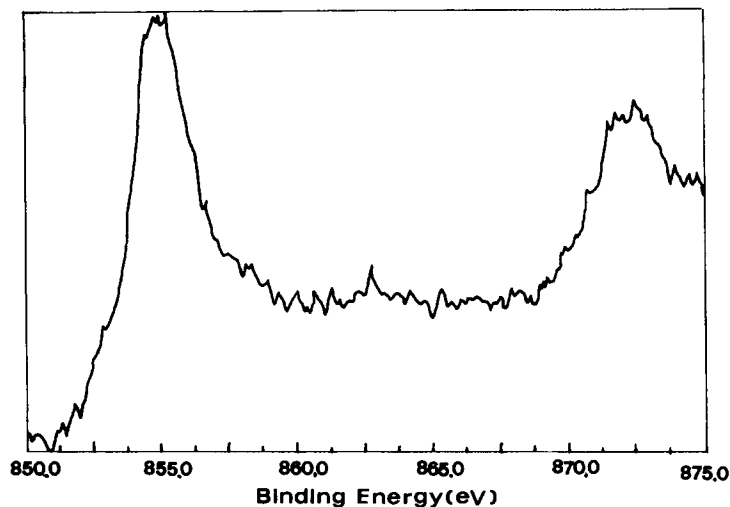


Figure 8(a) ESCA spectrum of unreduced nylon 4- Ni^{2+} chelate film.

Figure 8(b) ESCA spectrum of nylon 4- Ni^{2+} chelate film reduced by NaBH_4 aqueous solution.

9(c) and Figure 9(d), a "network" morphology is shown for the surface of the nylon- NiCl_2 and nylon- CoCl_2 metal chelate film, respectively. The continuous aggregation of metal particles on the surface of the reduced film is responsible for the conductivity of the metallized film.

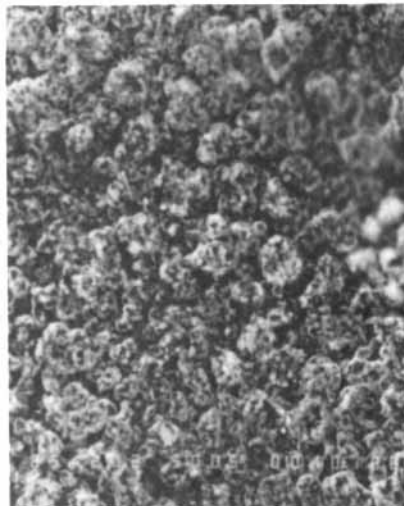
Effects of Metal Salts and Reducing Agents on the Tensile Properties of Polyamide Metal Chelate Films

As shown in Table VI, the tensile strength of unreduced nylon 4 (or nylon 6) chelate films was higher

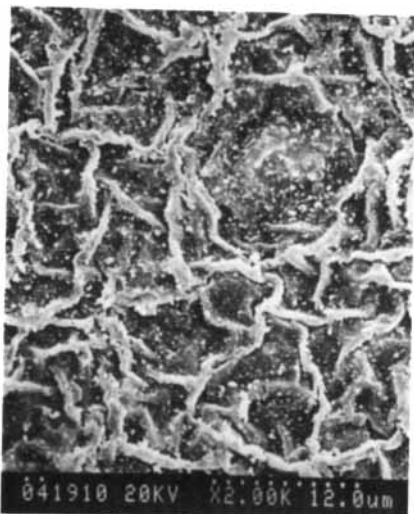
than for control nylon 4 (or nylon 6) film, but the elongation was much lower than for the control nylon film. The increase in tensile strength of polyamide metal chelate films could be attributed to the interpolymer chelates. The tensile strengths of reduced nylon 4 (or nylon 6)- CuCl_2 chelate films were slightly lower than for the unreduced nylon 4 (or nylon 6)- CuCl_2 chelate film, and the elongation was higher than for the unreduced polyamide metal chelate films. On average, there were no observable differences between the tensile properties of reduced polyamide metal chelate films and the control polyamide films. Therefore, these reduced polyamide



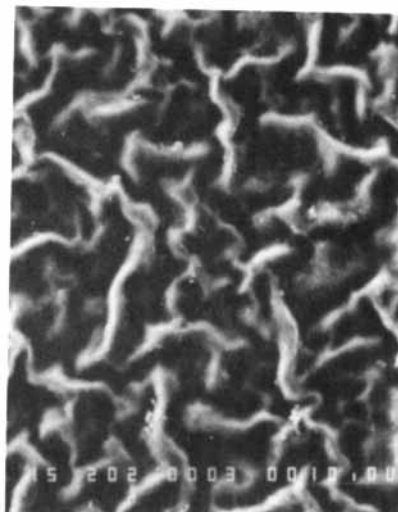
(a) Nylon 4-CuCl₂ Film before NaBH₄ Treatment



(b) Nylon 4-CuCl₂ Film after NaBH₄ Treatment



(c) Nylon 4-NiCl₂ Film after NaBH₄ Treatment



(d) Nylon 4-CoCl₂ Film after NaBH₄ Treatment

Figure 9 Scanning electron microscope photographs of nylon films.

Table VI Mechanical Properties of Nylon Films and Nylon Metal Chelate Films^a

Species	<i>F</i>	Tensile Strength (kg/cm ²)		Elongation (%)	
		Unreduced	Reduced	Unreduced	Reduced
Nylon 4	0	722.6	—	66.67	—
Nylon 4-CuCl ₂	0.05	733.3	682.1	65.83	59.17
	0.10	759.0	753.2	18.33	65.00
	0.125	1006.7	658.8	10.00	49.17
	0.15	916.7	584.6	15.42	17.92
Nylon 6	0	561.7	—	44.00	—
Nylon 6-CuCl ₂	0.06	511.1	440.0	10.83	13.33
	0.10	716.4	619.4	10.83	26.70
	0.15	654.8	584.4	12.50	30.00
	0.20	720.7	524.2	5.83	21.67

^a Drawing rate = 5.0 mm/min; drawing temperature = room temperature; load cell = 5.0 kg.

chelate films still maintained excellent tensile properties.

Proposed Structures for the Polyamide Metal Chelates

UV-visible and IR spectra confirmed metal chelate formation with metal ion coordinated with the amide groups of polyamide. Grant and Hay⁸ have shown that copper (II) could coordinate with the nitrogen atom of the amide group. Furthermore, according to investigations by Sumita⁹ and Taube,¹⁰ if the amount of CuCl₂ in the nylon 4-Cu²⁺ chelate film is over 10 wt % (*F* > 0.05), most of the Cu²⁺ ions are not chelated by nylon 4 but coordinated by Cl⁻. The Cl⁻ is considered as a bridging atom to form the activated complex. A proposed structure of this chelate is shown in Figure 10. Therefore, the surplus CuCl₂ in the activated complex can be easily reduced to metallic Cu on the film surface by NaBH₄ aqueous solution and results in excellent electrical conductivity.

As mentioned, only when the polyamide metal chelate film was reduced by NaBH₄ aqueous solution can these surplus metal ions in these films diffuse out by water and be further reduced to the metallic state by NaBH₄. But in the first paper of this series, poly(vinyl alcohol) (PVA) metal chelate film was shown to be reduced in various combinations of solvents and reducing agents, such as NaBH₄ in water, sodium (Na) in ethanol, etc., and all showed excellent electrical conductivity. The two different results, for polyamide metal chelate films and PVA metal chelate film, can be explained by the assumption that metal ions in the PVA-activated complex are oriented on the film surface, pointing toward the air. Therefore, the surplus metal ions in the PVA-activated complex can easily diffuse out in a variety of reducing agent solvents. The metal ions in the polyamide-activated complex were distributed throughout the interior of the film surface. Only strongly polar solvents such as water can cause metal ions in the polyamide metal chelate to diffuse out and then be reduced to the metallic state by NaBH₄.

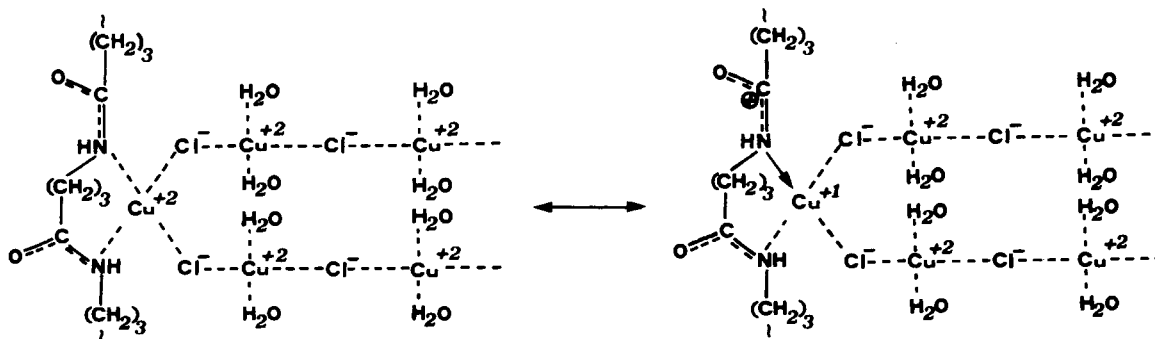


Figure 10 Proposed structure for the nylon 4-Cu²⁺ chelate responsible for conductivity.

Therefore, the affinity between solvents and metal ions plays an important role in the reduction to form conductive polymer films.

CONCLUSION

Electrically conducting polymer by this novel method can be prepared by the following steps:

1. Choose functional group-containing polymers such as polyamides, poly(vinyl alcohol), polyacrylonitrile, polyacrylamide, polyurethanes, polyamide-imides, etc.¹¹
2. Introduce metal salt solutions into the polymer solutions or soaking blank polymer films in metal salt solutions.
3. Form the polymer metal chelate films.
4. Treat with reducing agents in suitable solvents.
5. Reduce metal ions to metallic states on the polymer film surfaces.
6. Form polymer films with excellent electrical conductivity.

These processes are relatively simple and fast, and commercially available polymers can be used in this novel method. The mechanism of conduction will be reported in the near future.

The authors are indebted to the National Science Council of the Republic of China for financial support of this work

by grant NSC-79-0405-E033-02. They are also grateful to Prof. Keh-Ying Hsu, Chung Yuan Christian University for his cordial advice.

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Received February 21, 1990

Accepted March 8, 1990